

# Neha Thakur

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/120670/publications.pdf>

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12  
papers

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1163117

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#	ARTICLE	IF	CITATIONS
1	Universal direct patterning of colloidal quantum dots by (extreme) ultraviolet and electron beam lithography. <i>Nanoscale</i> , 2020, 12, 11306-11316.	5.6	27
2	Stability studies on a sensitive EUV photoresist based on zinc metal oxoclusters. <i>Journal of Micro/Nanolithography, MEMS, and MOEMS</i> , 2019, 18, 1.	0.9	19
3	Role of low-energy electrons in the solubility switch of Zn-based oxocluster photoresist for extreme ultraviolet lithography. <i>Physical Chemistry Chemical Physics</i> , 2021, 23, 16646-16657.	2.8	15
4	Heavy metal incorporated helium ion active hybrid non-chemically amplified resists: Nano-patterning with low line edge roughness. <i>AIP Advances</i> , 2017, 7, 085314.	1.3	12
5	Mixed-ligand zinc-oxoclusters: efficient chemistry for high resolution nanolithography. <i>Journal of Materials Chemistry C</i> , 2020, 8, 14499-14506.	5.5	11
6	Fluorescent Labeling to Investigate Nanopatterning Processes in Extreme Ultraviolet Lithography. <i>ACS Applied Materials &amp; Interfaces</i> , 2021, 13, 51790-51798.	8.0	10
7	Fluorine-Rich Zinc Oxoclusters as Extreme Ultraviolet Photoresists: Chemical Reactions and Lithography Performance. <i>ACS Materials Au</i> , 2022, 2, 343-355.	6.0	9
8	Direct Patterning of CsPbBr <sub>3</sub> Nanocrystals via Electron-Beam Lithography. <i>ACS Applied Energy Materials</i> , 2022, 5, 1672-1680.	5.1	8
9	Bottom-Up Nanofabrication with Extreme-Ultraviolet Light: Metal-Organic Frameworks on Patterned Monolayers. <i>ACS Applied Materials &amp; Interfaces</i> , 2021, 13, 43777-43786.	8.0	5
10	Photon-induced Fragmentation of Zinc-based Oxoclusters for EUV Lithography Applications. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2020, 33, 153-158.	0.3	5
11	New non-chemically amplified molecular resist design with switchable sensitivity for multi-lithography applications and nanopatterning. <i>Journal of Micromechanics and Microengineering</i> , 2017, 27, 125010.	2.6	4
12	Zinc-based metal oxoclusters: towards enhanced EUV absorptivity. , 2019, , .		2